

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	41	29/832.ccls. and nano\$	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/08 11:45
L3	1	29/832.ccls. and nano\$ and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/08 11:45
L4	3	(29/846,847).ccls. and nano\$ and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/08 11:47
L5	72	(430/5,319,321).ccls. and nano\$ and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/08 11:48
L6	17	(430/5,319,321).ccls. and nano\$ with pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/08 11:52
L7	33	nano\$ with pigment with (photomask\$3 or mask\$3 or resist\$3 or photoresist\$3)	US-PGPUB	OR	ON	2005/12/08 11:54
L8	32	nano\$ with pigment with (photomask\$3 or mask\$3 or resist\$3 or photoresist\$3) and substrate	US-PGPUB	OR	ON	2005/12/08 11:54
L9	1	nano\$ with pigment with (photomask\$3 or mask\$3 or resist\$3 or photoresist\$3) and (wiring adj substrate)	US-PGPUB	OR	ON	2005/12/08 11:54
S1	22	wiring adj substrate adj manufacturing adj method	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/19 13:23
S2	1	(wiring adj substrate adj manufacturing adj method) and photomask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/19 13:24
S3	1	(wiring adj substrate adj manufacturing adj method) and photomask and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/19 13:25
S4	0	photomask and (nano adj paricle)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/19 13:25
S5	11	photomask and (nano adj particle)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/19 13:25
S6	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	USPAT	OR	ON	2003/09/22 16:42

S7	1	photomask and (nano adj particle) and (black near (pigment or dye))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:19
S8	1214	29/832.ccls.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:05
S9	3	29/832.ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 19:37
S10	99	(toshihiko near tanaka).in.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:48
S11	1	(toshihiko near tanaka).in. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:49
S12	0	(toshihiko adj tanaka).in.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:50
S13	99	(tanaka adj toshihiko).in.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:50
S14	1	(tanaka adj toshihiko).in. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:50
S15	2	(kubo near masaharu).in. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:52
S16	1	(hattori near takashi).in. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 17:52
S17	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	USPAT	OR	ON	2003/09/22 17:56
S18	2	"6007969".URPN.	USPAT	OR	ON	2003/09/22 18:13
S19	17	(wiring adj substrate) and (nano)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:23
S20	769	(wiring) and (nano)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:58
S21	15	(wiring) and (nano) and photomask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:23
S22	264	(wiring) and (nano) and mask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:58

S23	222	(wiring) and (nano) and mask and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:59
S24	222	(method or process or step) and (wiring) and (nano) and mask and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:59
S25	14	(method or process or step) and (wiring near substrate) and (nano) and mask and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 18:59
S26	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	USPAT	OR	ON	2003/09/22 19:08
S27	2	29/846.ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 19:37
S28	2	29/847.ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/22 19:39
S29	4	430/319.ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 11:53
S30	23	(430/321,5).ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 12:42
S31	5	("5178978" "5371817" "5471552" "5550088" "5915051").PN.	USPAT	OR	ON	2003/09/24 11:57
S32	1924	mask and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 12:43
S33	1786	mask and nano and (conductive or conductor or wire or wiring or trace or track or line)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 12:44
S34	198	(photomask or (photo adj mask)) and nano and (conductive or conductor or wire or wiring or trace or track or line)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:05
S35	198	(method or process or step) and (photomask or (photo adj mask)) and nano and (conductive or conductor or wire or wiring or trace or track or line)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:03
S36	97	(method or process or step) with (photomask or (photo adj mask)) and nano and (conductive or conductor or wire or wiring or trace or track or line)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:06

S37	2	(method or process or step) with (photomask or (photo adj mask)) with nano and (conductive or conductor or wire or wiring or trace or track or line)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:05
S38	93	(method or process or step) with (photomask or (photo adj mask)) and nano and (conductive or conductor or wire or wiring or trace or track or line) and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:14
S39	10	(method or process or step) with (photomask or (photo adj mask)) and nano with (conductive or conductor or wire or wiring or trace or track or line) and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:14
S40	23	(method or process or step) and (photomask or (photo adj mask)) and nano and binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:18
S41	1326	(method or process or step) near (photomask or (photo adj mask))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:19
S42	1062	(method or process or step) near (photomask)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:19
S43	10	(method or process or step) near (photomask) and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:20
S44	130	(method or process or step) near (mask) and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:21
S45	4	(method or process or step) near (mask) with nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:26
S46	38	(method or process or step) with (mask) with nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:26
S47	1	(method or process or step) with (mask) with nano with glass	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 13:26
S48	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	USPAT	OR	ON	2003/09/24 13:29
S49	3	("4407695" "5510156" "5695658").PN.	USPAT	OR	ON	2003/09/24 13:56
S50	12	"5871870".URPN.	USPAT	OR	ON	2003/09/24 14:00

S51	86044	(method or process or step) with (mask or photomask or (photo adj mask))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:04
S52	38	(method or process or step) with (mask or photomask or (photo adj mask)) with nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:11
S53	3793	(method or process or step) with (mask or photomask or (photo adj mask)) and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:12
S54	596	(method or process or step) with (mask or photomask or (photo adj mask)) and (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:12
S55	22	(method or process or step) with (mask or photomask or (photo adj mask)) with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:18
S56	76	(mask or photomask or (photo adj mask)) with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:19
S57	65	(mask or photomask or (photo adj mask)) with (black adj pigment) and glass	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:19
S58	25	(mask or photomask or (photo adj mask)) with (black adj pigment) with glass	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 14:19
S59	1	("6412305").PN.	US-PGPUB; USPAT; USOCR; IBM_TDB	OR	OFF	2003/09/24 15:27
S60	1	("5746677").PN.	US-PGPUB; USPAT; USOCR; IBM_TDB	OR	OFF	2003/09/24 15:28
S61	136	mask and pigment and glass and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 15:31
S62	117	mask and pigment and glass and nano and (wire or wiring or track or lead or conductor or trace)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 15:31
S63	117	(method or process or step) and mask and pigment and glass and nano and (wire or wiring or track or lead or conductor or trace)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 15:32
S64	4	(method or process or step) and mask and (black adj pigment) and glass and nano and (wire or wiring or track or lead or conductor or trace or line or conductive) and layer	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 15:48
S65	3	"4465749".URPN.	USPAT	OR	ON	2003/09/24 15:39

S66	1	mask with (black adj pigment) and glass and nano and (wire or wiring or track or lead or conductor or trace or line or conductive) and layer	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 15:48
S67	43	mask with (black adj pigment) and glass and (wire or wiring or track or lead or conductor or trace or line or conductive) and layer	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 16:01
S68	1	mask with (black adj pigment) and glass and (wire or wiring or track or lead or conductor or trace or line or conductive) and layer and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 16:01
S69	4	mask with (black adj pigment) and glass and (wire or wiring or track or lead or conductor or trace or line or conductive) and layer and micro	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 16:01
S70	3660	photo adj etching	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:18
S71	24	(photo adj etching) with positive	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:19
S72	19	(photo adj etching) with positive and negative	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 18:32
S73	12	(mask or photomask or (photo adj mask)) with (black adj pigment) with glass and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:54
S74	1	carbon with (black adj pigment) with nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:55
S75	7	carbon with (black adj pigment) with meter	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:56
S76	1	carbon with (black adj pigment) with micro	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:56
S77	12	carbon with (black adj pigment) with micrometer	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 17:57
S78	12	(photo adj etching) with positive and negative and mask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 18:32
S79	10	(430/323).ccls. and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2003/09/24 20:49

S80	204	photomask and nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 13:32
S81	13	photomask same nano	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 13:57
S82	1356	nano and binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 13:57
S83	267	(nano adj particle) and binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 13:58
S84	36	(nano adj particle) same binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 13:58
S85	13	((nano adj particle) same binder) and (mask or photomask)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/01/27 14:13
S86	0	977/DIG1.ccls.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2004/11/19 14:05
S87	156	photomask and nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 13:11
S88	62	photomask same nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 10:49
S89	6	photomask with nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 10:36
S90	693	(photolithography or photomask\$3) and nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 11:09
S91	28	(photolithography or photomask\$3) with nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 11:50
S92	5	("4298448" "5066559" "5380362" "5559057" "5587111").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 11:27
S93	1	("5772905").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/20 11:28
S94	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 11:48

S95	89	(mask\$3) with nanoparticle	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 11:50
S96	5	("20020051928" "20020182541" "5478679" "6007969" "6174631").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 12:07
S97	5	("4298448" "5066559" "5380362" "5559057" "5587111").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 12:34
S98	2	("5466961" "5471075").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 12:47
S99	4	("20010023986" "20020088938" "6346189" "6528020").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 12:58
S10 0	56	photomask\$3 and nanoparticle and photolithography	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 13:29
S10 1	252	photomask\$3 and (nano or nanoparticle) and photolithography	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 13:29
S10 2	12	photomask\$3 with (nano or nanoparticle) and photolithography	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 13:29
S10 3	19	(photomask\$3 or (photoresist adj mask\$3)) with (nano or nanoparticle)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/20 13:41
S10 4	4	("5157002").URPN.	USPAT	OR	ON	2005/04/20 13:56
S10 5	5	("20020051928" "20020182541" "5478679" "6007969" "6174631").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/20 14:07
S10 6	4810	((light adj mask) or photomask or mask) and (nano or (nano adj particle) or nanoparticle or nanomolecul\$6)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 09:27
S10 7	671	((light adj mask) or photomask or mask) same (nano or (nano adj particle) or nanoparticle or nanomolecul\$6)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 09:27
S10 8	316	((light adj mask) or photomask or mask) with (nano or (nano adj particle) or nanoparticle or nanomolecul\$6)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 09:27
S10 9	210	((light adj mask) or photomask or mask) with (nano or (nano adj particle) or nanoparticle or nanomolecul\$6) and light	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 09:28

S11 0	15	((light adj mask) or photomask or mask) with (nano or (nano adj particle) or nanoparticle or nanomolecul\$6) and light and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 09:28
S11 1	5	("20020051928" "20020182541" "5478679" "6007969" "6174631").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 09:30
S11 2	367	photolithography and photomask and light and binder and glass	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 10:00
S11 3	163	photolithography and photomask and light and binder and glass and pigment	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 10:00
S11 4	155	photolithography and photomask and light and binder and glass and pigment and pattern	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 10:01
S11 5	118	photolithography and photomask and light and binder and glass and pigment and pattern and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 10:01
S11 6	118	photolithography and photomask and light and binder and glass and pigment and pattern and carbon and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 10:02
S11 7	5	("20020051928" "20020182541" "5478679" "6007969" "6174631").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:04
S11 8	18485	photomask	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:07
S11 9	2	photomask adj composition	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:04
S12 0	5	("20020051928" "20020182541" "5478679" "6007969" "6174631").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:21
S12 1	10	photomask with nano	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:53
S12 2	6	photomask with nanoparticle	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:49
S12 3	5	photomask and nanoparticle with binder	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 11:49
S12 4	5	photomask and (nanoparticle with binder)	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:07

S12 5	5176	"430"/\$.ccls. and photomask	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:07
S12 6	19	"430"/\$.ccls. and photomask and nanoparticle	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:11
S12 7	12	"430"/\$.ccls. and photomask and nanoparticle and binder	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:11
S12 8	5	("4298448" "5066559" "5380362" "5559057" "5587111").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 12:35
S12 9	10	(photomask with nano) and photomask	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 13:56
S13 0	4	(photomask with nanoparticle) and photomask and binder	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 13:04
S13 1	62	(photomask same nanoparticle) and photomask	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 13:57
S13 2	62	(photomask same nanoparticle) and photomask and nanoparticle	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 13:57
S13 3	6	(photomask same nanoparticle) and photomask and nanoparticle and binder	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 13:57
S13 4	9	("5046012" "5182718" "5210696" "5253182" "5441834" "5698859" "5862058" "5885734" "5969801").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 14:20
S13 5	1	("4465749").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/21 15:00
S13 6	0	("nanoparticleandbinder").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/21 15:01
S13 7	2893	nanoparticle and binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:01
S13 8	232	nanoparticle with binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:01
S13 9	38	nanoparticle near binder	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:02

S14 0	3	(nanoparticle near binder) and ((photoresist adj mask) or photomask)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:03
S14 1	9	(nanoparticle with binder) and ((photoresist adj mask) or photomask)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:05
S14 2	9	(nanoparticle with binder) and ((photoresist adj mask\$3) or photomask\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:06
S14 3	11	(nanoparticle same binder) and ((photoresist adj mask\$3) or photomask\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:36
S14 4	3	(nanoparticle with binder) same (shade adj pattern)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:36
S14 5	3	(nanoparticle with binder) same (shade)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:36
S14 6	5	(nanoparticle with binder) same (mask)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:37
S14 7	5	(nanoparticle with binder) same (mask\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:38
S14 8	4	(nanoparticle with binder) same (photomask\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:38
S14 9	62	(nanoparticle) same (photomask\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:38
S15 0	70	"430"/\$.ccls. and nanoparticle and (mask\$3 or photomask\$3 or (photoresist adj mask\$3))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:46
S15 1	32	"430"/\$.ccls. and nanoparticle and binder and (mask\$3 or photomask\$3 or (photoresist adj mask\$3))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:47
S15 2	8	"430"/\$.ccls. and (nanoparticle and binder) same (mask\$3 or photomask\$3 or (photoresist adj mask\$3))	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 15:47
S15 3	10	("3680028" "4352835" "4407695" "4664748" "4835392" "5256587" "5382315" "5466627" "5656349" "5871870").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/04/21 15:58
S15 4	9	("4352835").URPN.	USPAT	OR	ON	2005/04/21 15:59

S15 5	1	method adj dry adj etching adj photomask adj material	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:28
S15 6	17	(bellman-robert-a).in.	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:28
S15 7	9	(bellman-robert-a).in. and mask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:28
S15 8	2	(bellman-robert-a).in. and mask adj blank	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:29
S15 9	108	(photomask\$3 or (photoresist adj mask\$3)) with (pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:33
S16 0	23	(photomask\$3 or (photoresist adj mask\$3)) with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:37
S16 1	16	(photomask\$3 or (photoresist adj mask\$3)) with (black adj pigment) and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:33
S16 2	23	(photomask or (photoresist adj mask)) with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:42
S16 3	0	(photomask or (photoresist adj mask)) with (molecular adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:42
S16 4	108	(photomask or (photoresist adj mask)) with (pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:42
S16 5	74	(photomask or (photoresist adj mask)) with (pigment) and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:47
S16 6	20	(photomask or (photoresist adj mask)) with (pigment) and carbon and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:48
S16 7	20	(photomask or (photoresist adj mask)) with (pigment) and carbon and wiring and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 16:54
S16 8	28	(photomask or (photoresist adj mask)) same (pigment) and carbon and wiring and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:02
S16 9	44	(photomask or (photoresist adj mask)) with (composit\$3) and pigment and carbon and wiring and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:08

S17 0	10	(photomask or (photoresist adj mask)) with (fabricat\$3) and pigment and carbon and wiring and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:11
S17 1	23	(photomask or (photoresist adj mask)) with (fabricat\$3 or mak\$3 or creat\$3) and pigment and carbon and wiring and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:19
S17 2	5707	(photomask or (photoresist adj mask)) with (fabricat\$3 or mak\$3 or creat\$3)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:19
S17 3	153	(photomask or (photoresist adj mask)) with (fabricat\$3 or mak\$3 or creat\$3) and pigment and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:19
S17 4	135	(photomask or (photoresist adj mask)) with (fabricat\$3 or mak\$3 or creat\$3) and pigment and carbon and substrate	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:19
S17 5	23	(photomask or (photoresist adj mask)) with (fabricat\$3 or mak\$3 or creat\$3) and pigment and carbon and substrate and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:21
S17 6	34	(photomask or (photoresist adj mask)) with (produc\$3) and pigment and carbon and substrate and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:24
S17 7	352	(photomask or (photoresist adj mask)) and pigment and carbon and substrate and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:25
S17 8	28	(photomask or (photoresist adj mask)) same pigment and carbon and substrate and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:25
S17 9	11	((prepar\$3 or mak\$3 or fabricat\$3 or produc\$3) near (photomask or (photoresist adj mask))) and pigment and carbon and substrate and wiring	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:30
S18 0	123	((prepar\$3 or mak\$3 or fabricat\$3 or produc\$3) near (photomask or (photoresist adj mask))) and pigment and carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:30
S18 1	57	((prepar\$3 or mak\$3 or fabricat\$3 or produc\$3) near (photomask or (photoresist adj mask))) and pigment same carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/21 17:30
S18 2	334	(black adj pigment) with size	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 09:48

S18 3	199	(black adj pigment) with size same carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:34
S18 4	0	(black adj pigment) with size same carbon and photomask	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 09:53
S18 5	16	(black adj pigment) with size same carbon and mask\$3	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:00
S18 6	1	("20030135994").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/22 10:12
S18 7	1	("5344748").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/22 10:16
S18 8	1	("4415262").PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/22 10:33
S18 9	0	photomask and (black adj pigment) with size same carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:34
S19 0	377	photomask and (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:34
S19 1	44	photomask same (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:34
S19 2	22	photomask with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:37
S19 3	15	photomask with (pigment) same carbon	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/04/22 10:50
S19 4	4	((("4764432") or ("5134058") or ("5344748") or ("4415262"))).PN.	US-PGPUB; USPAT; IBM_TDB	OR	OFF	2005/04/22 10:51
S19 5	326	(mask or photomask or resist or photoresist) with (black adj pigment)	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 12:56
S19 6	17	(mask or photomask or resist or photoresist) with (black adj pigment) and nano\$	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:06
S19 7	2	(mask or photomask or resist or photoresist) with (black adj pigment) same percent\$3	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:10
S19 8	5	(mask or photomask or resist or photoresist) same (black adj pigment) same percent\$3	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:12

S19 9	187	(mask or photomask or resist or photoresist) and (black adj pigment) same percent\$3	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:12
S20 0	73	(mask or photomask or resist or photoresist) and (black adj pigment) with percent\$3	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:12
S20 1	26	(mask or photomask or resist or photoresist) and (black adj pigment) with percent\$3 and nano\$	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:39
S20 2	173	(mask or photomask or resist or photoresist) and (black near (carbon or pigment)) with percent\$3 and nano\$	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:39
S20 3	7	(mask or photomask or resist or photoresist) same (black near (carbon or pigment)) with percent\$3 and nano\$	US-PGPUB; USPAT; IBM_TDB	OR	ON	2005/12/07 13:39